### References cited herein:

- U.S. Patent No. 7,147,759 ("'759 Patent")
- D.V. Mozgrin, *et al*, <u>High-Current Low-Pressure Quasi-Stationary Discharge in a Magnetic Field: Experimental Research</u>, Plasma Physics Reports, Vol. 21, No. 5, 1995 ("Mozgrin")
- A. A. Kudryavtsev, *et al*, <u>Ionization relaxation in a plasma produced by a pulsed inert-gas discharge</u>, Sov. Phys. Tech. Phys. 28(1), January 1983 ("Kudryavtsev")

Claims 1-3, 5-10, 13-16, 18-20, 22-34, 37, 40-43 and 45-46, 48, 50	Mozgrin in view of Kudryavtsev
[1pre.] A magnetically enhanced sputtering source comprising:	The combination of Mozgrin with Kudryavtsev discloses a magnetically enhanced sputtering source.
	Mozgrin 403, right col, ¶4 ("Regime 2 was characterized by intense cathode sputtering")
	Mozgrin at Fig. 1
	(a) A Z
	E B 1
	3- January 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1
	(b) z
	3
	E I
	Fig. 1. Discharge device configurations: (a) planar magnetron; (b) shaped-electrode configuration. (1) Cathode; (2) anode; (3) magnetic system.
[1a.] an anode;	The combination of Mozgrin with Kudryavtsev discloses an anode.



Claims 1-3, 5-10, 13-16, 18-20, 22-34, 37, 40-43 and 45-46, 48, 50	Mozgrin in view of Kudryavtsev
	'759 Patent at Fig. 1 ("FIG. 1 illustrates a cross-sectional view of a known magnetron sputtering apparatus having a pulsed power source.")  '759 Patent at 3:40-41 ("an anode 130 is positioned in the vacuum chamber 104 proximate to the cathode assembly.")  Mozgrin at Fig. 1

Claims 1-3, 5-10, 13-16, 18-20, 22-34, 37, 40-43 and 45-46, 48, 50	Mozgrin in view of Kudryavtsev
[1b.] a cathode assembly that is positioned adjacent to the anode, the cathode assembly including a sputtering target;	Fig. 1. Discharge device configurations: (a) planar magnetron; (b) shaped-electrode configuration. (I) Cathode; (2) anode; (3) magnetic system.  The combination of Mozgrin with Kudryavtsev discloses a cathode assembly that is positioned adjacent to the anode, the cathode assembly including a sputtering target.  '759 Patent at Fig. 1  The combination of Mozgrin with Kudryavtsev discloses a cathode assembly including a sputtering target.  '759 Patent at Fig. 1  The combination of Mozgrin with Kudryavtsev discloses a cathode assembly including a sputtering target.  The combination of Mozgrin with Kudryavtsev discloses a cathode assembly including a sputtering target.  The combination of Mozgrin with Kudryavtsev discloses a cathode assembly including a sputtering target.  The combination of Mozgrin with Kudryavtsev discloses a cathode assembly including a sputtering target.  The combination of Mozgrin with Kudryavtsev discloses a cathode assembly including a sputtering target.  The combination of Mozgrin with Kudryavtsev discloses a cathode;  The combination of Mozgrin with Kudryavtsev discloses a cathode;  The combination of Mozgrin with Kudryavtsev discloses a cathode;  The combination of Mozgrin with Kudryavtsev discloses a cathode assembly that is positioned adjacent to the anode, the cathode assembly including a sputtering target.

Claims 1-3, 5-10, 13-16, 18-20, 22-34, 37, 40-43 and 45-46, 48, 50	Mozgrin in view of Kudryavtsev
	'759 Patent at 3:23-24 ("magnetron sputtering apparatus 100 also includes a cathode assembly 114 having a target material 116.")
	Mozgrin at 403, right col, ¶ 4 ("Regime 2 was characterized by intense cathode sputtering").
	Mozgrin at 403, right col, ¶ 4 ("The pulsed deposition rate of the cathode material").
	Mozgrin at Fig. 1
	E B 1
	(b) 2 B F
	Fig. 1. Discharge device configurations: (a) planar magnetron; (b) shaped-electrode configuration. (1) Cathode; (2) anode; (3) magnetic system.
[1c.] an ionization source that generates a weakly-ionized plasma proximate to the anode and the cathode assembly;	The combination of Mozgrin with Kudryavtsev discloses an ionization source that generates a weakly-ionized plasma proximate to the anode and the cathode assembly.
	'759 Patent at 6:30-32 ("The weakly-ionized plasma is also referred to as a pre-ionized plasma.")
	'759 Patent at claim 32 ("wherein the peak plasma density of the weakly-ionized plasma is less than about 10 <sup>12</sup> cm <sup>-3</sup> ").
	Mozgrin at 401, right col, ¶2 ("For pre-ionization, we used a stationary magnetron discharge; the discharge current ranged up to 300 mA We found out that only the regimes with magnetic



Claims 1-3, 5-10, 13-16, 18-20, 22-34, 37, 40-43 and 45-46, 48, 50	Mozgrin in view of Kudryavtsev
	field strength not lower than 400 G provided the initial plasma density in the $10^9 - 10^{11}$ cm <sup>-3</sup> range."). (emphasis added).
	Mozgrin at 401, left col, ¶ 1 ("The [plasma] discharge had an annular shape and was adjacent to the cathode."). (emphasis added)
	Mozgrin at 402, right col, ¶2 ("Figure 3 shows typical voltage and current oscillograms Part I in the voltage oscillogram represents the voltage of the stationary discharge (pre-ionization stage).").
	Mozgrin at Fig. 6
	(a) 7
	(9) 1)
	(b) 2
	Fig. 6. High-current quasi-stationary discharge regimes. (a) planar magnetron: (I) high-current magnetron regime $(p = 5 \times 10^{-3} \text{ Ar}, I_d = 70 \text{ A}, U_d = 900 \text{ V});$ (2) high-current diffuse regime $(p = 10^{-1} \text{ torr}, \text{ Ar}, I_d = 700 \text{ A}, U_d = 80 \text{ V});$ (3) are regime $(p = 10^{-1} \text{ Ar}, I_d = 1000 \text{ A}, U_d = 80 \text{ V});$ (3) are regime $(p = 10^{-1} \text{ Ar}, I_d = 1000 \text{ A}, U_d = 80 \text{ V});$ (b) Shaped-electrode system: (I) high-current diffuse regime $(p = 10^{-1} \text{ torr}, \text{ Ar}, I_d = 1000 \text{ A}, U_d = 90 \text{ C});$ (2) contracted are regime $(p = 10^{-1} \text{ torr}, \text{ Ar}, I_d = 1500 \text{ A}, U_d = 50 \text{ V}).$
[1d.] a magnet that is	The combination of Mozgrin with Kudryavtsev discloses a magnet
positioned to generate a magnetic field proximate	that is positioned to generate a magnetic field proximate to the weakly-ionized plasma, the magnetic field substantially trapping
to the weakly-ionized plasma, the magnetic	electrons in the weakly-ionized plasma proximate to the sputtering target.
field substantially	'759 Patent at 3:10-12 ("FIG. 1 shows a cross-sectional view of a



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